

L Number	Hits	Search Text	DB	Time stamp
1	2090	oxide same surface near3 charge	USPAT; US-PGPUB	2003/12/11 15:29
9	0	UV same charge same (DC and RF) same (electron adj beam)	USPAT; US-PGPUB	2003/12/11 15:29
2	66	(oxide same surface near3 charge) and hydrofluoric and silicon and dioxide	USPAT; US-PGPUB	2003/12/11 15:29
3	105	vapor and hydrofluoric and ((silicon adj dioxide) or "SiO.sub.2") and (UV adj radiation) and etch\$3	USPAT; US-PGPUB	2003/12/11 15:30
4	31	(vapor near2 (hydrofluoric or HF)) and ((silicon adj dioxide) or "SiO.sub.2") and (UV adj radiation) and etch\$3	USPAT; US-PGPUB	2003/12/11 15:36
5	90	(wafer and cleaning and HF and water and vapor) and (uv adj radiation)	USPAT; US-PGPUB	2003/12/11 15:30
6	32	(oxide same surface near3 charge) same (electron adj beam)	USPAT; US-PGPUB	2003/12/11 15:30
7	35	(oxide same surface same charge same positive) same (electron adj beam)	USPAT; US-PGPUB	2003/12/11 15:30
8	8	(dioxide same surface same charge same positive) same (electron adj beam)	USPAT; US-PGPUB	2003/12/11 15:30
10	25	charge same (DC and RF) same (electron adj beam)	USPAT; US-PGPUB	2003/12/11 15:30
11	262	(positive adj charge) same (electron adj beam)	USPAT; US-PGPUB	2003/12/11 15:30
12	961	(oxide same surface near3 charge) and (H2O or "H.sub.2O" or water)	USPAT; US-PGPUB	2003/12/11 15:30
13	173	(oxide same surface near3 charge) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)	USPAT; US-PGPUB	2003/12/11 15:31
14	107	((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)).ab.	USPAT; US-PGPUB	2003/12/11 15:35
15	1249	((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)).clm.	USPAT; US-PGPUB	2003/12/11 15:34
17	5	((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric) and monolayer).clm.	USPAT; US-PGPUB	2003/12/11 15:35
18	5	((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric) and monolayer).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:35
19	1548	((oxide or dioxide) and (H2O or "H.sub.2O" or water or isopropyl or methanol or alcohol) and (HF or hydrofluoric)).ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/12/11 15:36
20	172	(vapor near2 (hydrofluoric or HF)) and ((silicon adj dioxide) or "SiO.sub.2") and charge	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:37
21	46	(vapor near2 (hydrofluoric or HF)) and ((silicon adj dioxide) or "SiO.sub.2") and monolayer	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:37
22	46	(216/73).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:38
23	1069	(216/79).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:39

24	205	(216/80).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:39
25	1304	(438/706).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:40
26	323	(438/743).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:40
27	2135	(134/2).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:45
28	612	(134/31).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/12/11 15:46